Session Title:	[ThE1] Advanced Etching and Monitoring
Session Date:	November 14 (Thu.), 2024
Session Time:	09:00-10:00
Session Room:	Room E (Sicily Room, 1F, Paradise Hotel Busan)
Session Chair:	Prof. Won-Jun Lee (Sejong Univ., Korea)

[ThE1-1] 09:00-09:20

Ideal Si Etching with Ultra-Low Electron Temperature CF_4 Plasma

Junyoung Park, Nayeon Kim, Jung-Eun Choi, Min-Seok Kim, and Chin-Wook Chung (Hanyang Univ., Korea)

[ThE1-2] 09:20-09:40

In-situ Plasma Monitoring using Multiple Plasma Information (PI) for SiO_2 Etch Process with CF_4/O_2

Min Ho Kim, Jeong Eun Jeon, and Sang Jeen Hong (Myongji Univ., Korea)

[ThE1-3] 09:40-10:00

Optical Emission Spectroscopy Analysis (Line Ratio Method) Integrated with Electrical Method for Measuring Accurate Plasma Radical Density

Hyeon-Ho Nahm, Jeong-Hyun Lee, and Chung Chin Wook (Hanyang Univ., Korea)